



#1/Amended
PATENT

Customer No. 22,852
Attorney Docket No. 08244.0026

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Sun-oo KIM

Application No.: 09/739,743

Filed: December 20, 2000

For: METHOD FOR
MANUFACTURING INTERLAYER
DIELECTRIC LAYER IN A
SEMICONDUCTOR DEVICE

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) Group Art Unit: 2823

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) Examiner: W. Coleman
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Commissioner for Patents
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action dated January 31, 2002, please amend the
application as follows:

IN THE CLAIMS:

Please amend claims 1 and 7 as follows:

1. (Amended) A method for manufacturing an interlayer dielectric layer, the
method comprising the steps of:

a) setting an active matrix provided with a substrate and interconnections formed
on the substrate in a chamber;

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